

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of	:	Attorney Docket No. 2006_0570A
Koichi HASEGAWA et al.	:	Confirmation No. 1683
Serial No. 10/575,725	:	Group Art Unit 1733
Filed April 13, 2006	:	Examiner Janell Combs Morillo
SPUTTERING TARGET MATERIAL	:	Mail Stop: AF

RESPONSE TO FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is in response to the Official Action dated November 9, 2010.

Favorable reconsideration is respectfully requested.

The claims are 17-26 with claims 17-20 and 22-25 being withdrawn from consideration.

Claims 21 and 26 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Hensel (US 2,450,340) in view of Croce (US 6,841,012).

Present claim 21 is directed to a sputtering target material for forming a thin film having high reflectance.

Claim 26 is directed to the thin film formed from the material of claim 21.

The presently claimed thin film sputtering target materials are used e.g. for the production of thin films on optical recording media, as explained on pages 1-2 of the present specification.

High reflectance is desired in these films and sulphurization is a significant consideration in reducing reflectance as explained at page 10, line 10 to page 11, bottom line of the specification.

Hensel, on the other hand, relates to a completely different field of endeavor which is to wet tungsten with silver, copper or alloys thereof. Hensel achieves this by the addition of phosphorus to the silver or copper, or their alloys.